

INFORMATION DISCLOSURE STATEMENT

Applicant : Hada, et al.
App. No : 10/557,694
Filed : November 22, 2005
For : RESIN FOR PHOTORESIST
COMPOSITION, PHOTORESIST
COMPOSITION AND METHOD FOR
FORMING RESIST PATTERN
Examiner : Eoff, Anca
Art Unit : 1709

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 2 references to be considered by the Examiner. Also enclosed are 1 foreign patent references and/or non-patent literature as listed on the Information Disclosure Statement.

This Information Disclosure Statement is being filed before the mailing date of a final action and before the mailing of a Notice of Allowance. This Statement is accompanied by the fees set forth in 37 C.F.R. § 1.17(p). The Commissioner is hereby authorized to charge any additional fees which may be required or to credit any overpayment to Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: 9/26/07

By: 

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